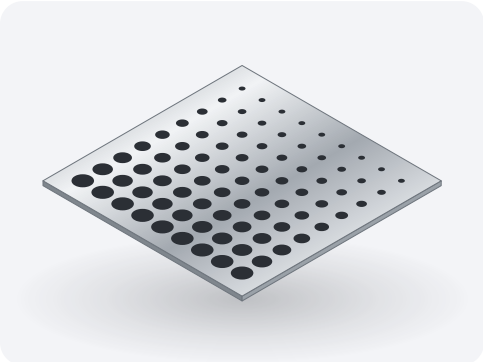
SERIES S51 · SHADOW MASKS

Deposition shadow masks



Laser-cut stainless steel stencils for patterning electrodes and test structures by thermal evaporation, e-beam or sputtering, without lithography. Standard thickness 100 µm; state 50, 150 or 200 µm when ordering.

- Stainless steel (SUS 304), stress-relieved and flattened
- Minimum feature 50 µm (≥ 20 µm electroformed Ni on request)
- Feature tolerance typically ± 10 µm
- Re-usable; matching clamp frames available

CONFIGURATIONS

Ref. No.	Pattern	Feature	Mask size	Typical use	Price
S5101	Dot array	Uniform Ø 0.1 – 2 mm	25 × 25 mm	Top contacts, diodes, solar cells	On request
S5102	Dot array	Graded Ø 0.1 – 2 mm	25 × 25 mm	Top contacts, diodes, solar cells	On request
S5103	Dot array	Uniform Ø 0.1 – 2 mm	50 × 50 mm	Top contacts, diodes, solar cells	On request
S5104	Square pads	0.2 – 2 mm	25 × 25 mm	Capacitors, probe pads	On request
S5105	Square pads	0.2 – 2 mm	50 × 50 mm	Capacitors, probe pads	On request
S5106	Lines / gratings	Line 50 µm – 1 mm	25 × 25 mm	Resistance, optical gratings	On request
S5107	Lines / gratings	Line 50 µm – 1 mm	50 × 50 mm	Resistance, optical gratings	On request
S5108	TLM contact lines	Gaps 20 – 500 µm	25 × 25 mm	Contact resistance (TLM)	On request
S5109	Interdigitated electrodes	Finger / gap 50 µm	25 × 25 mm	Gas, humidity and photodetectors	On request
S5110	Interdigitated electrodes	Finger / gap 50 µm	25 × 75 mm	Gas, humidity and photodetectors	On request
S5111	Interdigitated electrodes	Finger / gap 100 µm	25 × 25 mm	Gas, humidity and photodetectors	On request
S5112	Interdigitated electrodes	Finger / gap 100 µm	25 × 75 mm	Gas, humidity and photodetectors	On request
S5113	Interdigitated electrodes	Finger / gap 200 µm	25 × 25 mm	Gas, humidity and photodetectors	On request
S5114	Interdigitated electrodes	Finger / gap 200 µm	25 × 75 mm	Gas, humidity and photodetectors	On request
S5115	Hall bar	Channel 100 µm – 1 mm	25 × 25 mm	Carrier density, mobility	On request
S5116	Van der Pauw	Corner contacts 0.5 – 2 mm	10 × 10 mm	Sheet resistance, Hall	On request
S5117	Van der Pauw	Corner contacts 0.5 – 2 mm	25 × 25 mm	Sheet resistance, Hall	On request

Ref. No.	Pattern	Feature	Mask size	Typical use	Price
S5118	FET source / drain	Channel 20 – 200 µm	25 × 25 mm	Thin-film and 2D transistors	On request
S5119	Wafer format	Any standard pattern	Ø 100 mm (4")	Full-wafer patterning	On request
S5120	Mask-substrate clamp frame	—	10 × 10 mm	Holding mask and substrate together	On request
S5121	Mask-substrate clamp frame	—	25 × 25 mm	Holding mask and substrate together	On request
S5122	Mask-substrate clamp frame	—	4" wafer	Holding mask and substrate together	On request
S5123	Custom mask	From your DXF / DWG drawing	Up to 150 × 150 mm	Any	On request

Specifications are typical values; every lot ships with a Certificate of Conformance, and measured data are available on request. Prices on request.